

## **ABSTRACT**

A phase shift photomask is described, including a transparent substrate, and at least one isolated linear pattern, dense linear patterns and a transparent phase-shift region on the substrate. The isolated linear pattern includes a transparent end portion with a phase shift of  $180^\circ$  relative to the substrate. The transparent phase-shift region is located on the substrate adjacent to the ends of the dense linear patterns, and has a phase shift of  $90^\circ$  relative to the substrate.